This Sheet Has Been Replaced

ABSTRACT OF THE DISCLOSURE

A method for forming a photoresist film on a substrate, comprising: mounting a substrate on a supporting surface of a supporter so that a stepped portion is produced between the supporting surface and a top surface of the substrate; coating a photoresist on the top surface and a side surface of the substrate, the side surface showing up at the stepped portion; and then; blowing gas over the photoresist on the top surface to make the photoresist filmy.